

CLAIMS

1. A method for forming an organic thin film which comprises vaporizing a single film-forming component of organic material, transporting and feeding the resulting gas into a reaction chamber in which a substrate is placed, and depositing the single film-forming component of organic material as such on the surface of the substrate in the reaction chamber.

2. The method for forming an organic thin film as defined in Claim 1, wherein the substrate is kept cooled while the organic material is being deposited.

3. The method for forming an organic thin film as defined in Claim 1, wherein the deposition of the organic material is repeated so that film-forming components differing in composition are formed one over another.

4. The method for forming an organic thin film as defined in Claim 1, wherein the film-forming gas is transported and fed into the reaction chamber by using a carrier gas.